IN THE CLAIMS

Please amend the claims as follows:

Claims 1-15 (Canceled).

Claim 16 (Currently Amendment): A deposit shield arranged in a vacuum processing chamber in which plasma processing is to be performed on a substrate to be processed, and covering an inner side surface of the vacuum processing chamber to inhibit the inner side surface from being exposed to plasma, the deposit shield comprising:

an inner surface formed into a smooth curved side surface;

a notch portion formed to face a gate via which the substrate to be processed is loaded or unloaded;

a shutter formed to match the notch portion and make a same curved surface as the curved side surface;

a raising/lowering portion which raises/lowers the shutter;

an O-ring fitted in an inner surface side of an end surface of the shutter ~~that meets~~ facing the notch portion; and

a spiral seal fitted in an outer surface side thereof;

wherein when the shutter matches the notch portion, ~~the~~ an inner surface of the shutter and the ~~curved side~~ inner surface of the deposit shield make a ~~same~~ similar curved surface ~~and~~ so that the inner surfaces are formed on a same plane, whereby a uniformity in density of plasma generated in the plasma processing is maintained.

Claim 17 (Previously Presented): The deposit shield according to claim 16, wherein

the spiral seal electrically connects the deposit shield and the shutter to each other at a same ground potential, thereby preventing the plasma from detouring around to an outside of the deposit shield from a gap between the shutter and the notch portion that meet, and

the O-ring prevents particles generated from the spiral seal from scattering towards an inner side of the deposit shield.

Claim 18 (Previously Presented): The deposit shield according to claim 16, further comprising:

a stage on which the substrate to be processed is placed within the vacuum processing chamber; and

a disk-like exhaust plate arranged around the shutter,

wherein when the shutter is raised, the shutter of the deposit shield and the exhaust plate are brought into contact to each other to be electrically connected to each other.

Claim 19 (Previously Presented): The deposit shield according to claim 16, wherein the deposit shield and the shutter include respective heating mechanisms.

Claim 20 (Previously Presented): The deposit shield according to claim 16, wherein:

a cut end portion of the notch portion and the end surface of the shutter have respective L-shaped step portions which are fitted to each other;

an inner peripheral portion of the L-shaped step portion of the cut end portion of the notch portion extends, and an outer portion part of the L-shaped step portion of the end face of the shutter extends; and

plasma generated in the processing chamber is prevented from leaking between the notch portion and the end face of the shutter.

Claim 21 (New): The deposit shield according to Claim 16, wherein the end surface of the shutter configured to hold the O-ring is substantially perpendicular to the inner surface of the shutter.

Claim 22 (New): The deposit shield according to Claim 16,

wherein a cut end portion of the notch portion and the end surface of the shutter have respective complimentary step portions.

Claim 23 (New): The deposit shield according to Claim 22,

wherein each of the steps includes a plurality of portions substantially perpendicular to the inner surfaces of the deposit shield and shutter, and

wherein each of the steps further includes a portion substantially parallel to the inner surfaces of the deposit shield and shutter, whereby plasma generated in the processing chamber is prevented from leaking between the notch portion and the end face of the shutter.